IN THE CLAIMS

Please cancel claims 1 through 26.

Please add the following claims, numbered as claims 27 through 49.

27. (new) An illumination system, comprising:

an optical element having a raster element for directing a light beam having a wavelength ≤ 193 nm; and

a movable carrier upon which said optical element is arranged, for positioning said raster element relative to said light beam.

28. (new) The illumination system of claim 27, further comprising:

a reticle plane, wherein said reticle plane is defined by a y-direction and an x-direction, and

wherein said carrier is moveable in said x-direction.

29. (new) The illumination system of claim 27, further comprising:

a reticle plane within which a reticle is moveable in a first direction,

wherein said carrier is moveable in a second direction.

30. (new) The illumination system of claim 29, wherein said second direction is substantially perpendicular to said first direction.

31. (new) The illumination system of claim 27,

wherein said raster element is one of a plurality of raster elements on said optical element,

wherein said light beam impinges onto said optical element, and said plurality of raster elements partition said light beam into a plurality of light bundles, and

wherein said plurality of light bundles substantially overlap one another in a reticle plane.

32. (new) The illumination system of claim 27, wherein said optical element is one of a plurality of optical elements arranged on said carrier.

33. (new) The illumination system of claim 27, wherein said raster element is one of a plurality of raster elements on said optical element.

34. (new) An illumination system, comprising a plate having (a) a raster element situated thereon for directing a light beam having a wavelength $\leq$ 193 nm, and (b) an actuator for positioning said raster element relative to said light beam.

35. (new) The illumination system of claim 34, wherein said actuator changes an orientation of said raster element relative to said plate.

36. (new) The illumination system of claim 34, wherein said raster element is one of a plurality of raster elements on said plate.

37. (new) A system for illuminating a reticle in a reticle plane, comprising:

an optical element having a plurality of raster elements for directing a light beam having a wavelength $\leq$ 193 nm, and

a table upon which said optical element is situated, for moving said optical element relative to said light beam,

wherein said plurality of raster elements partition said light beam into a plurality of light bundles, and

wherein said plurality of light bundles substantially overlap one another in said reticle plane and define a ring field of illumination in said reticle plane.

38. (new) An illumination system, comprising:

an optical element having a plurality of raster elements, for partitioning a light beam having a wavelength ≤ 193 nm into a plurality of light bundles,

wherein said plurality of light bundles substantially overlap one another in a reticle plane of said illumination system and define a ring field of illumination in said reticle plane, and

wherein at least one of said plurality of raster elements is adjustable to change said ring field of illumination in said reticle plane.

39. (new) The illumination system of claim 38, wherein said at least one of said plurality of raster elements, when adjusted to change said ring field of illumination in said reticle plane, also changes an illumination in an exit pupil of said illumination system.

40. (new) The system of claim 38, wherein said at least one of said plurality of raster elements is tiltable.

41. (new) The system of claim 38, wherein said at least one of said plurality of raster elements is displaceable.

42. (new) The system of claim 38, wherein said at least one of said plurality of raster elements is replaceable.

43. (new) A method comprising:

adjusting at least one of a plurality of raster elements in an illumination system by employing a technique selected from the group consisting of:

(a) tilting said at least one of said plurality of raster elements,

(b) displacing said at least one of said plurality of raster elements, and

(c) replacing said at least one of said plurality of raster elements,

wherein said adjusting causes a change in a field of illumination.

44. (new) The method of claim 43, wherein said plurality of raster elements are for directing a beam of light having a wavelength of ≤ 193 nm.

45. (new) The method of claim 43, wherein said field of illumination is a ring field of illumination in a reticle plane in said illumination system.

46. (new) A method comprising:

adjusting at least one of a plurality of raster elements in an illumination system by employing a technique selected from the group consisting of:

(a) tilting said at least one of said plurality of raster elements,

(b) displacing said at least one of said plurality of raster elements, and

(c) replacing said at least one of said plurality of raster elements,

wherein said adjusting causes a change of an illumination of an exit pupil.

47. (new) A projection exposure apparatus, comprising:

(a) an illumination system for illuminating an object with light having a wavelength ≤ 193 nm,

wherein said illumination system includes (i) an optical element having a raster element, and (ii) a movable carrier upon which said optical element is arranged, for positioning said raster element relative to a beam of said light; and

(b) a projection objective for imaging said object onto a light sensitive substrate.

48. (new) The projection exposure apparatus of claim 47, wherein said object is a pattern-bearing mask.

49. (new) A method for manufacturing a microelectronic component, comprising using the projection exposure apparatus of claim 47.